

SPECIFICATION FOR PHOTORESIST SPINNER

1.0 General Requirements:

1.1 The following specification describes the requirements for the procurement of a Photoresist Spinner. The equipment shall provide process control for the application of multiple resist layers while controlling rotation rate/time profiles. All equipment shall be new and come with at least a one-year manufacturer's warranty.

2.0 Specific Requirements

The Photoresist Spinner shall provide the following capabilities:

- Chamber capable of handling specimens up to 7" x 7"
- Up to 12,000 rpm rotation speed
- Programmable control with at least 20 segment programming function
- Corrosion-proof body, shall not contain any exposed metallic parts within process chamber
- Clear lid with safety door interlock/latch
- Vacuum chucks for multiple size specimens. Shall be able to handles fragments, which can be handled using adaptors. Specimens from 5 mm to 200 mm in size will be used

3.0 Required components

- Process chamber
- Manual resist injector (single 5 mm syringe injector)
- Vacuum chuck for large specimens (up to 200 mm in size)
- Vacuum chuck for small specimens (less than 100 mm in size)
- Multiple fragment adaptors for irregular specimens (from 5 mm to 50 mm in size)
- Vacuum pump (pneumatic pump)

Suggested Product: WS-650-Mz-8NPP-Lite Single Wafer Spin Processor